## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Pat	ent Applica	ation of:					
Tae-hee	KIM						
Application	on No.: U	nassigned	Group Art Ur	Group Art Unit: Unassigned			
Filed: Ju	ıly 17, 200	3	Examiner: U	Jnassigned			
	r: PROJECTION SYSTEM EMPLOYING TWO LIGHT SOURCES OR TWO VALVES						
		INFORMATION DIS	SCLOSURE STATE	MENT			
	t Commiss ton, D.C.	ioner for Patents 20231			1 8		
Sir:			•				
	it is deeme	tent application. It is required material to the examina osures accompanying this Form PTO-1449. Copies of IDS citations. An English language col application or a PCT Int English language transle each non-English language Explanations of Relevan	ation of the subject as s Information Disclosion by of search report(sernational Search Ration (complete or reage publication.	application. sure Statement a s) from a counter eport. elevant portion(s)	are: rpart foreign )) attached to		
2.	☐ In a	providing a concise expl accordance with 37 CFR § lerstood to be the relevan	anation of each non	-English publicat planation of what	tion. t is presently		
	2a. 🗌	(Check appropriat satisfied because all nor enclosed "English-langu indicates the degree of r § 609, Minimum Require Part A(3): Concise Expla	age version of the selevance found by te ements for an Inform	publications were earch report or a the foreign office nation Disclosure	action which ". (See MPEP		
	2b. 🗌	set forth in the application		5, Odi EU.)			

	2d. 🔲		ed to each nor	nage translation (complete of n-English language publication eto.	
3.	to be, ma (other th	aterial to patentabilit an search report(s)	y nor a represe from a counter	cited in this Statement is, or entation that a search has be part foreign application or a prewith). 37 CFR §§ 1.97(g)	en made PCT
				Respectfully submitted,	·
				STAAS & HALSEY LLP	
Dated:	on, D.C. 2	., N.W., Suite 700 20005	Ву:	Michael D. Stein Registration No. 37,240	
Facsimile					

\*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.